


IN THE ABSTRACT OF THE DISCLOSURE

Please amend the Abstract of the disclosure as shown in the marked-up copy to read as follows:

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A main control system determines a mode of a focusing control based on both data representing the surface condition of a divided area and data for a shape of an illumination area on a wafer. Then, the main control system controls actuators based on detection results from a focus sensor, and performs the focusing control of a substrate stage for holding the wafer in respect to a projection optical system. Simultaneously with the focusing control, the main control system controls a wafer stage driving block to control the synchronous movement of a reticle stage and a substrate table. Thereby a pattern formed on a reticle is transferred onto the divided area on the wafer via the projection optical system. Not premising a high focusing control driving practicability, the pattern is transferred onto the substrate without serious deterioration of imaging performance.

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